

L Number	Hits	Search Text	DB	Time stamp
1	2	jp-2002116544-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/02 07:50
-	752	NAKANO-T NAKANO-TATSUYA	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/02 07:50
-	2	jp-10312060-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 09:08
-	2	jp-11109632-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 09:16
-	2	jp-09073173-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 09:20
-	2	jp-10003169-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 14:09
-	2	jp-08012626-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 09:29
-	2	jp-10083076-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 09:30
-	2	jp-07196743-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 09:33
-	0	jp-103169-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 09:34
-	2	jp-10003169-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 09:37
-	2	jp-08082925-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 09:40
-	2	jp-07234511-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 09:47
-	2	ep-663616-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/11 11:16
-	4	(NAKANO-T NAKANO-TATSUYA) and (acid adj (labile or cleavable or responsive or generat\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/20 17:43
-	1	wo-9961956-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 10:03
-	1	1998JP-0227336.prai. or 1998JP-0143535.prai.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 10:03

EAST
SEARCH

Do Not
REMOVE

-	1	wo-9961404-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 10:05
-	2	jp-2000019737-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 10:06
-	2	jp-11327148-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 10:07
-	2	jp-10221852-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 10:10
-	2	jp-10115925-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 10:13
-	2	jp-09297401-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 10:47
-	1	ep-326977-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 10:48
-	0	ep292219-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 10:48
-	2	ep-292219-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 10:50
-	9	((("6077644") or ("5929271") or ("4994344") or ("4666821"))).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 10:53
-	24	(NAKANO-T NAKANO-TATSUYA) and adamant\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/20 17:43
-	9986	(acid adj (labile or cleavable or responsive or generat\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 11:08
-	2056	((acid adj (labile or cleavable or responsive or generat\$3))) and (resin or binder) and \$5resist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 11:09
-	869	((acid adj (labile or cleavable or responsive or generat\$3))) and (resin or binder) and \$5resist) and 430/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 11:09
-	268	((((acid adj (labile or cleavable or responsive or generat\$3))) and (resin or binder) and \$5resist) and 430/\$.ccls.) and (monocyclic or polycyclic or alicyclic)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 11:09

-	268	((((acid adj (labile or cleavable or responsive or generat\$3))) and (resin or binder) and \$5resist) and 430/\$.ccls.) and (monocyclic or polycyclic or alicyclic)) not ((NAKANO-T NAKANO-TATSUYA) or jp-10312060-\$.did. or jp-11109632-\$.did. or jp-09073173-\$.did. or jp-10003169-\$.did. or jp-08012626-\$.did. or jp-10083076-\$.did. or jp-07196743-\$.did. or jp-103169-\$.did. or jp-10003169-\$.did. or jp-08082925-\$.did. or jp-07234511-\$.did. or ep-663616-\$.did. or ((NAKANO-T NAKANO-TATSUYA) and (acid adj (labile or cleavable or responsive or generat\$3))) or wo-9961956-\$.did. or (1998JP-0227336.prai. or 1998JP-0143535.prai.) or wo-9961404-\$.did. or jp-2000019737-\$.did. or jp-11327148-\$.did. or jp-10221852-\$.did. or jp-10115925-\$.did. or jp-09297401-\$.did. or ep-326977-\$.did. or ep292219-\$.did. or ep-292219-\$.did.))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 11:08
-	241	((((acid adj (labile or cleavable or responsive or generat\$3))) and (resin or binder) and \$5resist) and 430/\$.ccls.) and (monocyclic or polycyclic or alicyclic)) not ((NAKANO-T NAKANO-TATSUYA) or jp-10312060-\$.did. or jp-11109632-\$.did. or jp-09073173-\$.did. or jp-10003169-\$.did. or jp-08012626-\$.did. or jp-10083076-\$.did. or jp-07196743-\$.did. or jp-103169-\$.did. or jp-10003169-\$.did. or jp-08082925-\$.did. or jp-07234511-\$.did. or ep-663616-\$.did. or ((NAKANO-T NAKANO-TATSUYA) and (acid adj (labile or cleavable or responsive or generat\$3))) or wo-9961956-\$.did. or (1998JP-0227336.prai. or 1998JP-0143535.prai.) or wo-9961404-\$.did. or jp-2000019737-\$.did. or jp-11327148-\$.did. or jp-10221852-\$.did. or jp-10115925-\$.did. or jp-09297401-\$.did. or ep-326977-\$.did. or ep292219-\$.did. or ep-292219-\$.did.))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 11:09
-	3087	(acid adj (labile or cleavable or responsive))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 11:09
-	522	((acid adj (labile or cleavable or responsive))) and (resin or binder) and \$5resist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 11:09
-	133	(((acid adj (labile or cleavable or responsive))) and (resin or binder) and \$5resist) and (monocyclic or polycyclic or alicyclic)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 11:09
-	105	(((acid adj (labile or cleavable or responsive))) and (resin or binder) and \$5resist) and (monocyclic or polycyclic or alicyclic)) and 430/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/04/15 15:35
-	78	((((acid adj (labile or cleavable or responsive))) and (resin or binder) and \$5resist) and (monocyclic or polycyclic or alicyclic)) and 430/\$.ccls.) and (acid near generat\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/11/06 08:21
-	36	(CLARKE-YVETTE CLARKE-YVETTE-M) and (resist or photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/11/06 08:21
-	61	CLARKE-YVETTE CLARKE-YVETTE-M	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 11:27

-	2	("5968713").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 13:10
-	19	pinanone	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 13:10
-	1	("6218569").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/04/23 14:04
-	119	(((((acid adj (labile or cleavable or responsive))) and (resin or binder) and \$5resist) and (monocyclic or polycyclic or alicyclic)) and 430/\$.ccls.) and (acid near generat\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/11/06 08:23
-	58	(CLARKE-YVETTE CLARKE-YVETTE-M) and (resist or photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/11/06 08:22
-	30	(NAKANO-T NAKANO-TATSUYA) and adamant\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/20 17:43
-	206	(((((acid adj (labile or cleavable or responsive))) and (resin or binder) and \$5resist) and (monocyclic or polycyclic or alicyclic)) and 430/\$.ccls.) and (acid near generat\$3)) ((CLARKE-YVETTE CLARKE-YVETTE-M) and (resist or photoresist)) ((NAKANO-T NAKANO-TATSUYA) and adamant\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/11/06 08:23
-	57	(((((acid adj (labile or cleavable or responsive))) and (resin or binder) and \$5resist) and (monocyclic or polycyclic or alicyclic)) and 430/\$.ccls.) and (acid near generat\$3)) ((CLARKE-YVETTE CLARKE-YVETTE-M) and (resist or photoresist)) ((NAKANO-T NAKANO-TATSUYA) and adamant\$4)) and @pd>=20010331	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/04/15 15:36
-	149	(((((acid adj (labile or cleavable or responsive))) and (resin or binder) and \$5resist) and (monocyclic or polycyclic or alicyclic)) and 430/\$.ccls.) and (acid near generat\$3)) ((CLARKE-YVETTE CLARKE-YVETTE-M) and (resist or photoresist)) ((NAKANO-T NAKANO-TATSUYA) and adamant\$4)) not ((((((acid adj (labile or cleavable or responsive))) and (resin or binder) and \$5resist) and (monocyclic or polycyclic or alicyclic)) and 430/\$.ccls.) and (acid near generat\$3)) ((CLARKE-YVETTE CLARKE-YVETTE-M) and (resist or photoresist)) ((NAKANO-T NAKANO-TATSUYA) and adamant\$4)) and @pd>=20010331)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/04/15 15:36
-	254	(adamant\$4 anthrac\$4 tricyclodecan\$5) adj methacrylate	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/11/06 10:15

-	250	((adamant\$4 anthrac\$4 tricyclodecan\$5) adj methacrylate) not (((((((acid adj (labile or cleavable or responsive))) and (resin or binder) and \$5resist) and (monocyclic or polycyclic or alicyclic)) and 430/\$.ccls.) and (acid near generat\$3)) ((CLARKE-YVETTE CLARKE-YVETTE-M) and (resist or photoresist)) ((NAKANO-T NAKANO-TATSUYA) and adamant\$4)) not (((((((acid adj (labile or cleavable or responsive))) and (resin or binder) and \$5resist) and (monocyclic or polycyclic or alicyclic)) and 430/\$.ccls.) and (acid near generat\$3)) ((CLARKE-YVETTE CLARKE-YVETTE-M) and (resist or photoresist)) ((NAKANO-T NAKANO-TATSUYA) and adamant\$4)) and @pd>=20010331))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/11/06 10:15
-	248	((adamant\$4 anthrac\$4 tricyclodecan\$5) adj methacrylate) not (((((((acid adj (labile or cleavable or responsive))) and (resin or binder) and \$5resist) and (monocyclic or polycyclic or alicyclic)) and 430/\$.ccls.) and (acid near generat\$3)) ((CLARKE-YVETTE CLARKE-YVETTE-M) and (resist or photoresist)) ((NAKANO-T NAKANO-TATSUYA) and adamant\$4)) and @pd>=20010331))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/11/06 10:15
-	4	(NAKANO-T NAKANO-TATSUYA) and (acid adj (labile or cleavable or responsive or generat\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/04/15 15:36
-	34	(NAKANO-T NAKANO-TATSUYA) and adamant\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/04/15 15:36
-	177	(((((acid adj (labile or cleavable or responsive))) and (resin or binder) and \$5resist) and (monocyclic or polycyclic or alicyclic)) and 430/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/04/15 15:37
-	107	((((((acid adj (labile or cleavable or responsive))) and (resin or binder) and \$5resist) and (monocyclic or polycyclic or alicyclic)) and 430/\$.ccls.) and (acid near generat\$3)) ((CLARKE-YVETTE CLARKE-YVETTE-M) and (resist or photoresist)) ((NAKANO-T NAKANO-TATSUYA) and adamant\$4)) and @pd>=20010331	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/04/15 15:37
-	58	isobornyl same polycyclic	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/04/15 15:56
-	12	((spiro adj ring) (terpene adj ring) (steroid adj bile adj acid) (digitaloid adj ring) (camphor adj ring) (triterpene adj ring)) same (tricyclic tetracyclic (ring adj assembly))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/04/15 16:01

-	29	((("2002034704") or ("2002031720") or ("2002031719") or ("6348297") or ("2002015913") or ("2002009668") or ("2002009667") or ("2002009666") or ("2002007031") or ("2002006582") or ("2002004569") or ("2002004178") or ("2001051316") or ("2001051315") or ("2001049075") or ("2001046641") or ("2001044072") or ("2001044071") or ("2001044070") or ("2001038971") or ("2001036593") or ("2001035394") or ("2001033994") or ("2001033990") or ("2001033987") or ("6306554") or ("2001031421") or ("6303266") or ("2001026901") or ("2001024763") or ("6294309") or ("2001023050") or ("2001024763") or ("6294309") or ("2001023050") or ("6291130") or ("6284429") or ("6280911") or ("6280898") or ("6280897") or ("2001016298") or ("2001014428") or ("6270941") or ("6265131") or ("6248920") or ("2001003772") or ("2001003640") or ("6245485") or ("6239231") or ("6225476") or ("6207342") or ("6200725") or ("6156481") or ("6136501") or ("6087063") or ("6077644") or ("6054254") or ("6042991") or ("6013416") or ("6010826") or ("6239231") or ("6280897") or ("5968713") or ("5929271") or ("5910392") or ("2002042016") or ("6348297") or ("6042991") or ("6248920") or ("6329125") or ("5910392"))).PN.	USPAT; US-PGPUB	2002/04/16 10:28
-	1	("6245485").PN.	USPAT	2002/04/16 14:40
-	1	("6368227").PN.	USPAT	2002/04/16 14:46
-	1	("6280897").PN.	USPAT	2002/04/16 14:46
-	2	us-20020115883-\$.did. us-20010014428-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/11 11:03
-	2	("6348297").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/11 11:03
-	0	("00001 2").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/11 11:03
-	4	(us-20020115883-\$.did. us-20010014428-\$.did.) `(("6348297").PN.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/11 11:09
-	1	1999JP-0315264.prai. 1999JP-0092990.prai.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/11 11:10
-	7	((("5585507") or ("5691111") or ("5635332") or ("5756850"))).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/11 11:10
-	953	NAKANO-T NAKANO-TATSUYA	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/11 11:16
-	8	(NAKANO-T NAKANO-TATSUYA) and (acid adj (labile or cleavable or responsive or generat\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/20 17:44
-	49	(NAKANO-T NAKANO-TATSUYA) and adamant\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/11 11:49

-	44	((NAKANO-T NAKANO-TATSUYA) and adamant\$4) not(((NAKANO-T NAKANO-TATSUYA) and (acid adj (labile or cleavable or responsive or generat\$3))) (((("5585507") or ("5691111") or ("5635332") or ("5756850")).PN.) (1999JP-0315264.prai. 1999JP-0092990.prai.) ((us-20020115883-\$did. us-20010014428-\$did.) ((("6348297").PN.)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/20 17:43
-	44	((NAKANO-T NAKANO-TATSUYA) and adamant\$4) not(((NAKANO-T NAKANO-TATSUYA) and (acid adj (labile or cleavable or responsive or generat\$3))) (((("5585507") or ("5691111") or ("5635332") or ("5756850")).PN.) (1999JP-0315264.prai. 1999JP-0092990.prai.) ((us-20020115883-\$did. us-20010014428-\$did.) ((("6348297").PN.)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/11 12:40
-	2	jp-10143535-\$did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/11 12:40
-	4	((("6004720") or ("6235851")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/09/11 12:58
-	1	("6245485").PN.	USPAT;	2002/09/11 12:58
-	9	(NAKANO-T NAKANO-TATSUYA) and (acid adj (labile or cleavable or responsive or generat\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/20 17:43
-	60	(NAKANO-T NAKANO-TATSUYA) and adamant\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/20 17:43
-	60	(NAKANO-T NAKANO-TATSUYA) and adamant\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/20 17:43
-	9	(NAKANO-T NAKANO-TATSUYA) and (acid adj (labile or cleavable or responsive or generat\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/20 17:44
-	63	((NAKANO-T NAKANO-TATSUYA) and (acid adj (labile or cleavable or responsive or generat\$3))) ((NAKANO-T NAKANO-TATSUYA) and adamant\$4) ((NAKANO-T NAKANO-TATSUYA) and adamant\$4) ((NAKANO-T NAKANO-TATSUYA) and (acid adj (labile or cleavable or responsive or generat\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/20 17:51
-	0	1-hydroxy-3-1-acryloxyloxy-12-dimehtylpropyl adj adamantine	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/20 17:52
-	0	1-hydroxy-3-1-acryloxyloxy-12-dimehtylpropyladamantine	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/20 17:52
-	0	1-hydroxy-3-1-acryloxyloxy-12-dimethylpropyladamantine	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/20 17:53
-	0	1-hydroxy-3-1-acryloxyloxy-12-dimethylpropyl adj adamantine	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/20 17:53
-	0	1-hydroxy-3-1-acryloxyloxy-12-dimethylpropyl adj adamantane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/20 17:53
-	0	2-hydroxy-6-acryloyloxy-tricyclo\$5decane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/20 17:53

-	0	2-hydroxy6acryloyloxytricyclo\$5decane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/20 17:53
-	0	2hydroxy6acryloyloxytricyclo\$5decane	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/20 18:14
-	2	("6440636").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/20 18:41
-	0	6440636.URPN.	USPAT	2003/05/20 18:26
-	2	("5968713" "6303266").PN.	USPAT	2003/05/20 18:27
-	2	("6218569").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/05/20 18:41
-	0	6218569.URPN.	USPAT	2003/05/20 18:43
-	0	6218569.URPN.	USPAT	2003/05/20 18:43

PAT-NO: JP02002116544A
DOCUMENT-IDENTIFIER: JP 2002116544 A
TITLE: POSITIVE TYPE PHOTORESIST COMPOSITION
PUBN-DATE: April 19, 2002

INVENTOR-INFORMATION:

NAME	COUNTRY
SATO, KENICHIRO	N/A

ASSIGNEE-INFORMATION:

NAME	COUNTRY
FUJI PHOTO FILM CO LTD	N/A

APPL-NO: JP2000310761

APPL-DATE: October 11, 2000

INT-CL (IPC): G03F007/039, C08F232/00 , C08K005/00 ,
C08L045/00 , G03F007/004
, H01L021/027

ABSTRACT:

PROBLEM TO BE SOLVED: To provide a positive type photoresist composition less liable to cause development defects in the production of a semiconductor device, excellent in adhesion on an inorganic antireflection film and excellent also in exposure margin (in particular, exposure margin in the case of isolated lines), sensitivity change with age, etc.

SOLUTION: The positive type photoresist composition contains (A) a resin containing repeating structural units with norbornene and repeating structural units containing a specified alicyclic hydrocarbon structure

and having a
velocity of dissolution in an alkali developing solution
increased by the
action of an acid and (B) a compound which generates the acid
when irradiated
with active light or radiation.

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=>Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 964 AND 970 AND 1015 AND 1051 AND 2067

L1 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\09463059.str

L2 STRUCTURE UPLOADED

=> que L2 AND L1

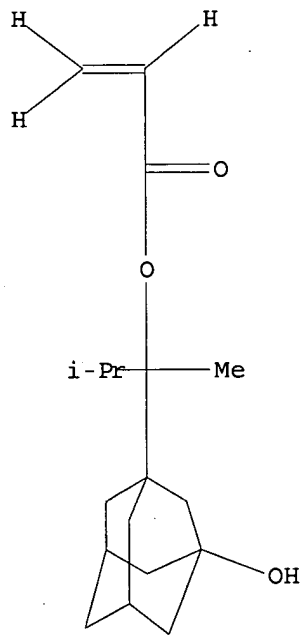
L3 QUE L2 AND L1

=> d

L3 HAS NO ANSWERS

L1 SCR 964 AND 970 AND 1015 AND 1051 AND 2067

L2 STR



Compound of ex. 15

G1 Me,H

G2 H,Ak,Cy

G3 Cy,Ak

Structure attributes must be viewed using STN Express query preparation.

L3 QUE ABB=ON PLU=ON L2 AND L1

=> s l3 sss sam

SAMPLE SEARCH INITIATED 07:44:46 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 0 TO ITERATE

100.0% PROCESSED 0 ITERATIONS

0 ANSWERS

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**

BATCH **COMPLETE**
PROJECTED ITERATIONS: 0 TO 0
PROJECTED ANSWERS: 0 TO 0

L4 0 SEA SSS SAM L2 AND L1

=> FIL CAPLUS HCAPLUS USPATFULL USPAT2
COST IN U.S. DOLLARS .

	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	0.40	0.61

FILE 'CAPLUS' ENTERED AT 07:44:52 ON 02 JUN 2003
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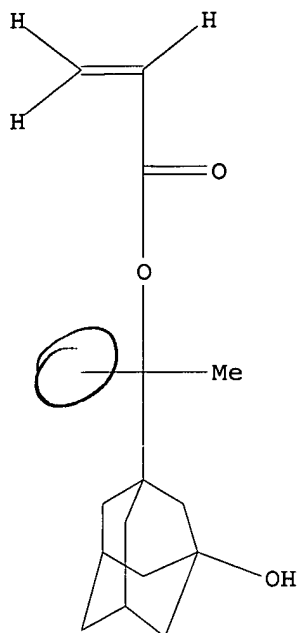
FILE 'HCAPLUS' ENTERED AT 07:44:52 ON 02 JUN 2003
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=> s l4
L5 0 L4

=> d
 L8 HAS NO ANSWERS
 L6 SCR 963 AND 970 AND 1015 AND 2067
 L7 STR



just C

G1 Me,H
 G2 H,Ak,Cy
 G3 Cy,Ak

Structure attributes must be viewed using STN Express query preparation.
 L8 QUE ABB=ON PLU=ON L7 AND L6

=> s l8 sss sam
 SAMPLE SEARCH INITIATED 07:46:22 FILE 'REGISTRY'
 SAMPLE SCREEN SEARCH COMPLETED - 2 TO ITERATE

100.0% PROCESSED 2 ITERATIONS 2 ANSWERS
 SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
 BATCH **COMPLETE**
 PROJECTED ITERATIONS: 2 TO 124
 PROJECTED ANSWERS: 2 TO 124

L9 2 SEA SSS SAM L7 AND L6

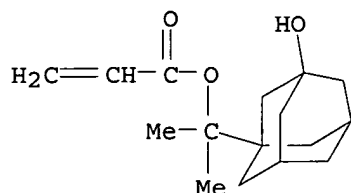
=> d

L9 ANSWER 1 OF 2 REGISTRY COPYRIGHT 2003 ACS
 RN 450410-08-9 REGISTRY
 CN 2-Propenoic acid, 3,5-dihydroxytricyclo[3.3.1.1.3,7]dec-1-yl ester, polymer
 with 1-(3-hydroxytricyclo[3.3.1.1.3,7]dec-1-yl)-1-methylethyl 2-propenoate
 (9CI) (CA INDEX NAME)
 MF (C16 H24 O3 . C13 H18 O4)x
 CI PMS
 PCT Polyacrylic

SR CA
LC STN Files: CA, CAPLUS, USPATFULL

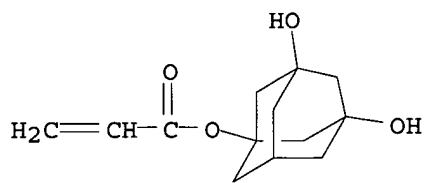
CM 1

CRN 262608-27-5
CMF C16 H24 O3



CM 2

CRN 216581-85-0
CMF C13 H18 O4



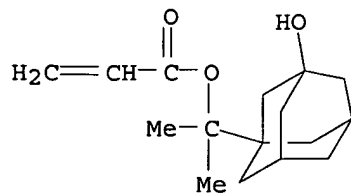
1 REFERENCES IN FILE CA (1957 TO DATE)
1 REFERENCES IN FILE CAPLUS (1957 TO DATE)

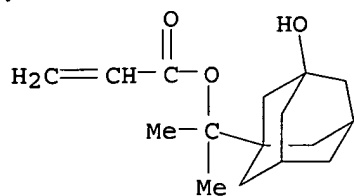
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L9 ANSWER 1 OF 2 REGISTRY COPYRIGHT 2003 ACS
RN 450410-08-9 REGISTRY
CN 2-Propenoic acid, 3,5-dihydroxytricyclo[3.3.1.1.3,7]dec-1-yl ester, polymer with 1-(3-hydroxytricyclo[3.3.1.1.3,7]dec-1-yl)-1-methylethyl 2-propenoate (9CI) (CA INDEX NAME)
MF (C16 H24 O3 . C13 H18 O4)x
CI PMS
PCT Polyacrylic
SR CA
LC STN Files: CA, CAPLUS, USPATFULL

CM 1

CRN 262608-27-5
CMF C16 H24 O3

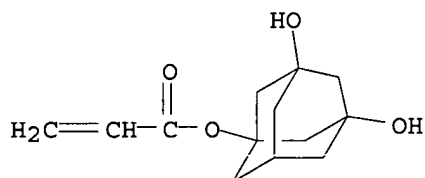




CM 2

CRN 216581-85-0

CMF C13 H18 O4



1 REFERENCES IN FILE CA (1957 TO DATE)

1 REFERENCES IN FILE CAPLUS (1957 TO DATE)

L9 ANSWER 2 OF 2 REGISTRY COPYRIGHT 2003 ACS

RN 412015-88-4 REGISTRY

CN 2-Propenoic acid, 1-(3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl)-1-methylethyl ester, polymer with 2,5-furandione, 1,2,3,4,4a,5,8,8a-octahydro-1,4:5,8-dimethanonaphthalene and tetrahydro-2-oxo-3-furanyl 2-propenoate (9CI) (CA INDEX NAME)

MF (C16 H24 O3 . C12 H16 . C7 H8 O4 . C4 H2 O3)x

CI PMS

PCT Polyacrylic, Polyester, Polyester formed, Polyether, Polyvinyl

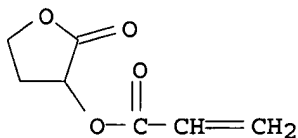
SR CA

LC STN Files: CA, CAPLUS

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CRN 328249-37-2

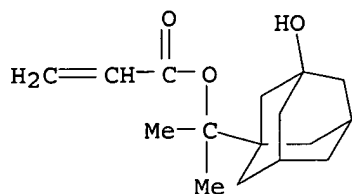
CMF C7 H8 O4



CM 2

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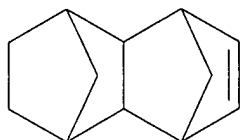
CMF C16 H24 O3



CM 3

CRN 21635-90-5

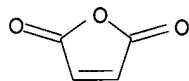
CMF C12 H16



CM 4

CRN 108-31-6

CMF C4 H2 O3



1 REFERENCES IN FILE CA (1957 TO DATE)
1 REFERENCES IN FILE CAPLUS (1957 TO DATE)

=> FIL CAPLUS HCAPLUS USPATFULL USPAT2
COST IN U.S. DOLLARS

SINCE FILE ENTRY	TOTAL SESSION
5.44	11.26

FULL ESTIMATED COST

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FILE 'USPATFULL' ENTERED AT 07:46:44 ON 02 JUN 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPAT2' ENTERED AT 07:46:44 ON 02 JUN 2003
CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> d his

(FILE 'HOME' ENTERED AT 07:44:07 ON 02 JUN 2003)

FILE 'REGISTRY' ENTERED AT 07:44:17 ON 02 JUN 2003
L1 SCREEN 964 AND 970 AND 1015 AND 1051 AND 2067
L2 STRUCTURE UPLOADED
L3 QUE L2 AND L1
L4 0 S L3 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 07:44:52 ON 02 JUN 2003
L5 0 S L4

FILE 'REGISTRY' ENTERED AT 07:45:52 ON 02 JUN 2003
L6 SCREEN 963 AND 970 AND 1015 AND 2067
L7 STRUCTURE UPLOADED
L8 QUE L7 AND L6
L9 2 S L8 SSS SAM

FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 07:46:44 ON 02 JUN 2003

=> s l9
L10 5 L9

=> duplicates remove l10
DUPLICATE PREFERENCE IS 'CAPLUS, HCAPLUS, USPATFULL'
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n
PROCESSING COMPLETED FOR L10
L11 2 DUPLICATE REMOVE L10 (3 DUPLICATES REMOVED)

=> d l11 1-2 ibib hitstr abs

L11 ANSWER 1 OF 2 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 1
ACCESSION NUMBER: 2002:654986 CAPLUS
DOCUMENT NUMBER: 137:192769
TITLE: Polymeric compound and resin composition for photoresist
INVENTOR(S): Ushirogouchi, Toru; Okino, Takeshi; Asakawa, Koji; Shida, Naomi; Funaki, Yoshinori; Tsutsumi, Kiyoharu; Takaragi, Akira; Inoue, Keizo
PATENT ASSIGNEE(S): Kabushiki Kaisha Toshiba, Japan; Daicel Chemical Industries, Ltd.
SOURCE: U.S., 24 pp.
CODEN: USXXAM
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 6440636	B1	20020827	US 2000-703677	20001102

PRIORITY APPLN. INFO.: US 2000-703677 20001102

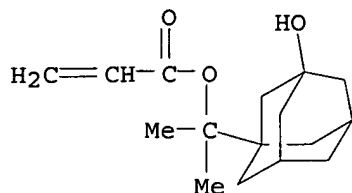
IT 450410-08-9P
RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(polymeric compd. and resin compn. for photoresist)

RN 450410-08-9 CAPLUS
CN 2-Propenoic acid, 3,5-dihydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl ester, polymer with 1-(3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl)-1-methylethyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 262608-27-5
CMF C16 H24 O3

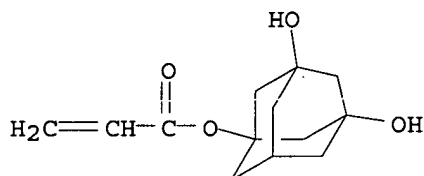
11-02-00



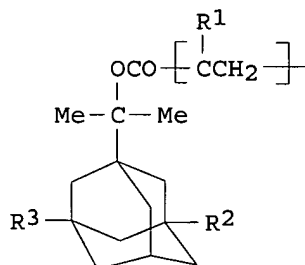
CM 2

CRN 216581-85-0

CMF C13 H18 O4



GI



I

AB A polymeric compd. includes at least one monomeric unit of I (R1 = H, Me group; R2,3 = H, hydroxyl group). The polymeric compd. may include the monomeric unit and at least one monomeric unit selected from monomeric units represented by II, III (R1 = H, Me group; R4,5 = H, hydroxy, oxo, carboxyl group; R4,5 are not concurrently hydrogen atoms; R7,8 = H, hydroxyl, oxo group). The polymeric compd. have a high etching resistance in addn. to satisfactory transparency, alkali-soly., and adhesion.

REFERENCE COUNT: 13 THERE ARE 13 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L11 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2003 ACS

DUPLICATE 2

ACCESSION NUMBER: 2002:292089 CAPLUS

DOCUMENT NUMBER: 136:316934

TITLE: Positive-working photoresist composition for fabrication of semiconductor device

INVENTOR(S): Sato, Kenichiro

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 51 pp.

CODEN: JKXXAF

DOCUMENT TYPE:

Patent

LANGUAGE:

Japanese

FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

4/19/02

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002116544	A2	20020419	JP 2000-310761	20001011
PRIORITY APPLN. INFO.:			JP 2000-310761	20001011
OTHER SOURCE(S):			MARPAT 136:316934	

10/11/00

IT 412015-88-4

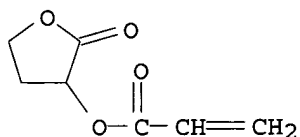
RL: TEM (Technical or engineered material use); USES (Uses)
(pos.-working photoresist compn. for fabrication of semiconductor device)

RN 412015-88-4 CAPLUS

CN 2-Propenoic acid, 1-(3-hydroxytricyclo[3.3.1.1^{3,7}]dec-1-yl)-1-methylethyl ester, polymer with 2,5-furandione, 1,2,3,4,4a,5,8,8a-octahydro-1,4:5,8-dimethanonaphthalene and tetrahydro-2-oxo-3-furanyl 2-propenoate (9CI)
(CA INDEX NAME)

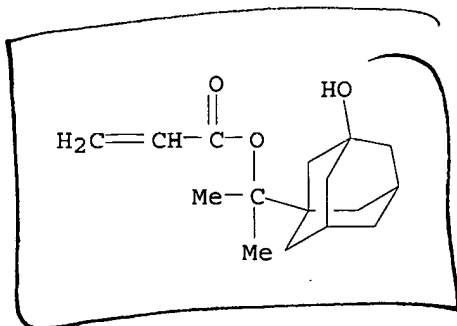
CM 1

CRN 328249-37-2
CMF C7 H8 O4



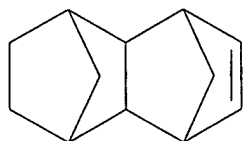
CM 2

CRN 262608-27-5
CMF C16 H24 O3



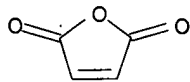
CM 3

CRN 21635-90-5
CMF C12 H16

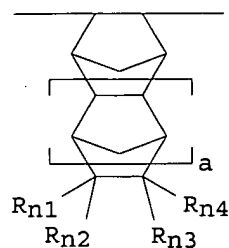


CM 4

CRN 108-31-6
CMF C4 H2 O3



GI



I

AB The photoresist compn. contains a resin whose soly. rate in alk. developer increases by reaction with an acid and having a norbornene-based repeating unit I ($a = 0, 1$) and a OH group-contg. alicyclic hydrocarbyl ester group, and a compd. generating an acid upon irradiation with an actinic ray or radiation. The photoresist provides little fault pattern having improved adhesion to an inorg. antireflection film.